

SPI Supplies Plasma Prep™ X



A tabletop, anisotropic plasma etcher, designed to meet the needs of the solid-state electronics industry.
just a click away...2spi.com/ppx



SPI Supplies Division of **STRUCTURE PROBE, Inc.**

P.O. Box 656 • West Chester, PA 19381-0656 USA
Phone: 1-610-436-5400 • 1-800-2424-SPI (USA and Canada) • Fax: 1-610-436-5755 • 2spi.com • E-mail: sales@2spi.com



SPI Supplies Plasma Prep™ X

The Plasma Prep™ X utilizes an anisotropic, parallel plate design to eliminate “undercutting” samples during the etching process. The system incorporates solid-state technology, an integrated vacuum gauge, and dual gas inputs for precise gas blending.

Typical Applications:

- Glass passivation layer removal
- Electron microscopy sample preparation
- Replace wet chemical etching
- Remove photo resist residue
- Remove organic contaminants
- Failure analysis

System Specifications:

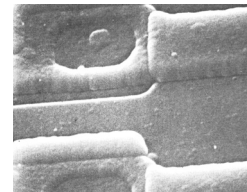
- 13.56 MHz RF plasma
- Parallel plate design reaction chamber
- Adjustable power, from 1–150 watts
- Water cooled
- Integrated vacuum gauge
- Independently adjustable, dual gas inputs
- Size: 19.5" W × 13.5" D × 18" H
(50 cm W × 34 cm D × 46 cm H)
- Chamber size: 10" diameter × 5.5" high
- CE Certified and RoHS Compliant

System Includes:

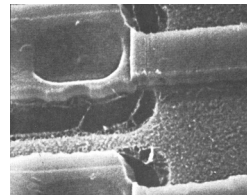
- Plasma Prep X main unit
- Either Pyrex or quartz chamber
- Vacuum hose (NW 25)
- Power cord
- Water re-circulator

Site Requirements:

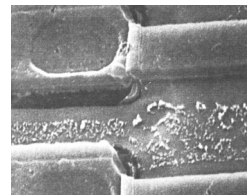
- Process gas(es)
- Vacuum pump
- Electrical Power: 110 V, 50/60 Hz or 220 V, 50/60 Hz



Glass passivation layer
(before etching)



After isotropic etching
with Plasma Prep II (30 min)



After anisotropic etching
with Plasma Prep X (90 min)



The complete source for all your microscopy needs...
2spi.com